Steven George

List of Publications by Year in Descending Order

449 papers	33,459 citations	90 h-index	165 g-index
481 ext. papers	35,650 ext. citations	5.3 avg, IF	7.75 L-index

#	Paper	IF	Citations
449	Spontaneous etching of B2O3 by HF gas studied using infrared spectroscopy, mass spectrometry, and density functional theory. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2022**, 40, 022601	2.9	2
448	Atomic layer etching of ferroelectric hafnium zirconium oxide thin films enables giant tunneling electroresistance. *Applied Physics Letters*, **2022**, 120, 122901	3.4	3
447	Deposit and etchback approach for ultrathin Al2O3 films with low pinhole density using atomic layer deposition and atomic layer etching. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2021**, 39, 062602	2.9	3
446	Prediction and Validation of the Process Window for Atomic Layer Etching: HF Exposure on TiO2. *Journal of Physical Chemistry C*, **2021**, 125, 25589-25599	3.8	4
445	Thermal atomic layer etching of germanium-rich SiGe using an oxidation and "conversion-etch" mechanism. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2021**, 39, 022602	2.9	4
444	Atomic layer deposition of hafnium and zirconium oxyfluoride thin films. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2021**, 39, 022403	2.9	1
443	Thermal atomic layer etching: A review. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2021**, 39, 030801	2.9	26
442	Thermal atomic layer etching of amorphous and crystalline Al2O3 films. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2021**, 39, 042602	2.9	5
441	Hollow cathode plasma electron source for low temperature deposition of cobalt films by electron-enhanced atomic layer deposition. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2021**, 39, 042403	2.9	0
440	Conversion reactions in atomic layer processing with emphasis on ZnO conversion to Al2O3 by trimethylaluminum. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2021**, 39, 021001	2.9	4
439	Area-selective molecular layer deposition of nylon 6,2 polyamide: Growth on carbon and inhibition on silica. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2021**, 39, 023204	2.9	8
438	Molecular layer deposition of Nylon 2,6 polyamide polymer on flat and particle substrates in an isothermal enclosure containing a rotary reactor. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2021**, 39, 052405	2.9	1
437	Molecular layer deposition for the fabrication of desalination membranes with tunable metrics. *Desalination*, **2021**, 520, 115334	10.3	5
436	Smoothing surface roughness using Al2O3 atomic layer deposition. *Applied Surface Science*, **2021**, 569, 150878	6.7	5
435	Mechanisms of Thermal Atomic Layer Etching. *Accounts of Chemical Research*, **2020**, 53, 1151-1160	24.3	41
434	Thermal Atomic Layer Etching of Gallium Oxide Using Sequential Exposures of HF and Various Metal Precursors. *Chemistry of Materials*, **2020**, 32, 5937-5948	9.6	8
433	Thermal atomic layer etching of silicon nitride using an oxidation and "conversion etch" mechanism. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2020**, 38, 022607	2.9	18

432	Effect of crystallinity on thermal atomic layer etching of hafnium oxide, zirconium oxide, and hafnium zirconium oxide. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2020**, 38, 022608	2.9	14
431	Atomic layer deposition of aluminum oxyfluoride thin films with tunable stoichiometry. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2020**, 38, 022407	2.9	3
430	Thermal etching of AlF3 and thermal atomic layer etching of Al2O3. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2020**, 38, 022603	2.9	13
429	Volatile Etch Species Produced during Thermal Al2O3 Atomic Layer Etching. *Journal of Physical Chemistry C*, **2020**, 124, 287-299	3.8	24
428	ZrO2 Monolayer as a Removable Etch Stop Layer for Thermal Al2O3 Atomic Layer Etching Using Hydrogen Fluoride and Trimethylaluminum. *Chemistry of Materials*, **2020**, 32, 10055-10065	9.6	1
427	Continuous polymer films deposited on top of porous substrates using plasma-enhanced atomic layer deposition and molecular layer deposition. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2020**, 38, 052409	2.9	5
426	Probing the Atomic-Scale Structure of Amorphous Aluminum Oxide Grown by Atomic Layer Deposition. *ACS Applied Materials & Interfaces*, **2020**, 12, 22804-22814	9.5	12
425	Spatial Molecular Layer Deposition of Ultrathin Polyamide To Stabilize Silicon Anodes in Lithium-Ion Batteries. *ACS Applied Energy Materials*, **2019**, 2, 4135-4143	6.1	14
424	Effect of HF Pressure on Thermal Al2O3 Atomic Layer Etch Rates and Al2O3 Fluorination. *Journal of Physical Chemistry C*, **2019**, 123, 10346-10355	3.8	33
423	SF4 as the Fluorination Reactant for Al2O3 and VO2 Thermal Atomic Layer Etching. *Chemistry of Materials*, **2019**, 31, 3624-3635	9.6	16
422	Thermal atomic layer etching of crystalline GaN using sequential exposures of XeF2 and BCl3. *Applied Physics Letters*, **2019**, 114, 243103	3.4	23
421	Thermal Atomic Layer Etching of Al2O3, HfO2, and ZrO2 Using Sequential Hydrogen Fluoride and Dimethylaluminum Chloride Exposures. *Journal of Physical Chemistry C*, **2019**, 123, 18455-18466	3.8	25
420	In Situ Thermal Atomic Layer Etching for Sub-5 nm InGaAs Multigate MOSFETs. *Nano Letters*, **2019**, 19, 5159-5166	11.5	19
419	Growth of cobalt films at room temperature using sequential exposures of cobalt tricarbonyl nitrosyl and low energy electrons. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2019**, 37, 060906	2.9	7
418	Improving Powder Characteristics by Surface Modification Using Atomic Layer Deposition. *Organic Process Research and Development*, **2019**, 23, 2362-2368	3.9	8
417	Thermal Atomic Layer Etching of Amorphous and Crystalline Hafnium Oxide, Zirconium Oxide, and Hafnium Zirconium Oxide **2019**,		3
416	Spatial molecular layer deposition of polyamide thin films on flexible polymer substrates using a rotating cylinder reactor. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2018**, 36, 01A117	2.9	17
415	Electron-enhanced atomic layer deposition of silicon thin films at room temperature. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2018**, 36, 01A118	2.9	15

414	Spatial atomic layer deposition for coating flexible porous Li-ion battery electrodes. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2018**, 36, 01A123	2.9	16
413	Electron-Enhanced Atomic Layer Deposition of Boron Nitride Thin Films at Room Temperature and 100 °C. *Journal of Physical Chemistry C*, **2018**, 122, 9455-9464	3.8	22
412	Efficient Capacitive Deionization Using Thin Film Sodium Manganese Oxide. *Journal of the Electrochemical Society*, **2018**, 165, A2330-A2339	3.9	11
411	Electron-Enhanced Atomic Layer Deposition of Boron Nitride Thin Films at Room Temperature and 100 °C. *Journal of Physical Chemistry C*, **2018**, 122,	3.8	1
410	First Transistor Demonstration of Thermal Atomic Layer Etching: InGaAs FinFETs with sub-5 nm Fin-width Featuring in situ ALE-ALD **2018**,		17
409	Thermal Atomic Layer Etching of Silicon Using O2, HF, and Al(CH3)3 as the Reactants. *Chemistry of Materials*, **2018**, 30, 8465-8475	9.6	32
408	Thermal atomic layer etching of HfO2 using HF for fluorination and TiCl4 for ligand-exchange. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2018**, 36, 061504	2.9	29
407	Rapid atomic layer etching of Al2O3 using sequential exposures of hydrogen fluoride and trimethylaluminum with no purging. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2018**, 36, 061508	2.9	22
406	Thermal Atomic Layer Etching of ZnO by a "Conversion-Etch" Mechanism Using Sequential Exposures of Hydrogen Fluoride and Trimethylaluminum. *Chemistry of Materials*, **2017**, 29, 1183-1191	9.6	57
405	Thermal Atomic Layer Etching of SiO by a "Conversion-Etch" Mechanism Using Sequential Reactions of Trimethylaluminum and Hydrogen Fluoride. *ACS Applied Materials & Interfaces*, **2017**, 9, 10296-10307	9.5	73
404	Competition between AlO atomic layer etching and AlF atomic layer deposition using sequential exposures of trimethylaluminum and hydrogen fluoride. *Journal of Chemical Physics*, **2017**, 146, 052819	3.9	32
403	Coating Solution for High-Voltage Cathode: AlF Atomic Layer Deposition for Freestanding LiCoO Electrodes with High Energy Density and Excellent Flexibility. *ACS Applied Materials & Interfaces*, **2017**, 9, 9614-9619	9.5	47
402	Surface modification of acetaminophen particles by atomic layer deposition. *International Journal of Pharmaceutics*, **2017**, 525, 160-174	6.5	31
401	Progress and prospects in nanoscale dry processes: How can we control atomic layer reactions?. *Japanese Journal of Applied Physics*, **2017**, 56, 06HA02	1.4	21
400	WO and W Thermal Atomic Layer Etching Using "Conversion-Fluorination" and "Oxidation-Conversion-Fluorination" Mechanisms. *ACS Applied Materials & Interfaces*, **2017**, 9, 34435-34447	9.5	47
399	Thermal Atomic Layer Etching of Titanium Nitride Using Sequential, Self-Limiting Reactions: Oxidation to TiO2 and Fluorination to Volatile TiF4. *Chemistry of Materials*, **2017**, 29, 8202-8210	9.6	52
398	Atomic Layer Deposition of Zn(O,S) Alloys Using Diethylzinc with H2O and H2S: Effect of Exchange Reactions. *Journal of Physical Chemistry C*, **2017**, 121, 18643-18652	3.8	17
397	Atomic layer deposition-A novel method for the ultrathin coating of minitablets. *International Journal of Pharmaceutics*, **2017**, 531, 47-58	6.5	13

396	Stabilizing an amorphous V2O5/carbon nanotube paper electrode with conformal TiO2 coating by atomic layer deposition for lithium ion batteries. *Journal of Materials Chemistry A*, **2016**, 4, 537-544	13	49
395	Rapid Growth of Crystalline Mn5O8 by Self-Limited Multilayer Deposition using Mn(EtCp)2 and O3. *ACS Applied Materials & Interfaces*, **2016**, 8, 18560-9	9.5	14
394	Band Diagram and Rate Analysis of Thin Film Spinel LiMn2O4 Formed by Electrochemical Conversion of ALD-Grown MnO. *Advanced Functional Materials*, **2016**, 26, 7895-7907	15.6	31
393	Molecular Layer Deposition for Surface Modification of Lithium-Ion Battery Electrodes. *Advanced Materials Interfaces*, **2016**, 3, 1600762	4.6	49
392	Enhanced Methanol Oxidation with Annealed Atomic Layer Deposited Platinum Nanoparticles on Carbon Nanotubes. *Journal of the Electrochemical Society*, **2016**, 163, F1-F10	3.9	28
391	Electron Enhanced Growth of Crystalline Gallium Nitride Thin Films at Room Temperature and 100 °C Using Sequential Surface Reactions. *Chemistry of Materials*, **2016**, 28,	9.6	29
390	Spatial atomic layer deposition on flexible porous substrates: ZnO on anodic aluminum oxide films and Al2O3 on Li ion battery electrodes. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2016**, 34, 01A146	2.9	24
389	Thermal atomic layer etching of crystalline aluminum nitride using sequential, self-limiting hydrogen fluoride and Sn(acac)2 reactions and enhancement by H2 and Ar plasmas. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2016**, 34, 050603	2.9	50
388	Prospects for Thermal Atomic Layer Etching Using Sequential, Self-Limiting Fluorination and Ligand-Exchange Reactions. *ACS Nano*, **2016**, 10, 4889-94	16.7	90
387	Atomic Layer Deposition of Metal Fluorides Using HF–Pyridine as the Fluorine Precursor. *Chemistry of Materials*, **2016**, 28, 2022-2032	9.6	44
386	Cross-linked aluminum dioxybenzene coating for stabilization of silicon electrodes. *Nano Energy*, **2016**, 22, 202-210	17.1	24
385	Trimethylaluminum as the Metal Precursor for the Atomic Layer Etching of Al2O3 Using Sequential, Self-Limiting Thermal Reactions. *Chemistry of Materials*, **2016**, 28, 2994-3003	9.6	65
384	Selectivity in Thermal Atomic Layer Etching Using Sequential, Self-Limiting Fluorination and Ligand-Exchange Reactions. *Chemistry of Materials*, **2016**, 28, 7657-7665	9.6	63
383	Atomic layer deposition of ultrathin platinum films on tungsten atomic layer deposition adhesion layers: Application to high surface area substrates. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2015**, 33, 01A130	2.9	33
382	Mitigating irreversible capacity losses from carbon agents via surface modification. *Journal of Power Sources*, **2015**, 275, 605-611	8.9	12
381	Atomic Layer Deposition of AlF3 Using Trimethylaluminum and Hydrogen Fluoride. *Journal of Physical Chemistry C*, **2015**, 119, 14185-14194	3.8	59
380	Structure and Reactivity of Alucone-Coated Films on Si and Li(x)Si(y) Surfaces. *ACS Applied Materials & Interfaces*, **2015**, 7, 11948-55	9.5	33
379	Surface-coating regulated lithiation kinetics and degradation in silicon nanowires for lithium ion battery. *ACS Nano*, **2015**, 9, 5559-66	16.7	99

378	Amorphous Ultrathin TiO2Atomic Layer Deposition Films on Carbon Nanotubes as Anodes for Lithium Ion Batteries. *Journal of the Electrochemical Society*, **2015**, 162, A974-A981	3.9	46
377	Mechanism of Thermal Al2O3 Atomic Layer Etching Using Sequential Reactions with Sn(acac)2 and HF. *Chemistry of Materials*, **2015**, 27, 3648-3657	9.6	50
376	Electrical and thermal conduction in ultra-thin freestanding atomic layer deposited W nanobridges. *Nanoscale*, **2015**, 7, 17923-8	7.7	5
375	Doped Si nanoparticles with conformal carbon coating and cyclized-polyacrylonitrile network as high-capacity and high-rate lithium-ion battery anodes. *Nanotechnology*, **2015**, 26, 365401	3.4	7
374	Effect of Al2O3 Coating on Stabilizing LiNi0.4Mn0.4Co0.2O2 Cathodes. *Chemistry of Materials*, **2015**, 27, 6146-6154	9.6	149
373	Atomic Layer Etching of HfO2Using Sequential, Self-Limiting Thermal Reactions with Sn(acac)2and HF. *ECS Journal of Solid State Science and Technology*, **2015**, 4, N5013-N5022	2	70
372	Silicon algae with carbon topping as thin-film anodes for lithium-ion microbatteries by a two-step facile method. *Journal of Power Sources*, **2015**, 274, 252-259	8.9	27
371	Spatial atomic layer deposition on flexible substrates using a modular rotating cylinder reactor. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2015**, 33, 01A132	2.9	33
370	Atomic Layer Etching of AlF3 Using Sequential, Self-Limiting Thermal Reactions with Sn(acac)2 and Hydrogen Fluoride. *Journal of Physical Chemistry C*, **2015**, 119, 25385-25393	3.8	31
369	Growth and Characterization of Al2O3 Atomic Layer Deposition Films on sp(2)-Graphitic Carbon Substrates Using NO2/Trimethylaluminum Pretreatment. *ACS Applied Materials & Interfaces*, **2015**, 7, 12030-7	9.5	23
368	Pyrolysis of Alucone Molecular Layer Deposition Films Studied Using In Situ Transmission Fourier Transform Infrared Spectroscopy. *Journal of Physical Chemistry C*, **2015**, 119, 14603-14612	3.8	40
367	Amorphous Ultrathin SnO2 Films by Atomic Layer Deposition on Graphene Network as Highly Stable Anodes for Lithium-Ion Batteries. *ACS Applied Materials & Interfaces*, **2015**, 7, 27735-42	9.5	49
366	Sodium Charge Storage in Thin Films of MnO2Derived by Electrochemical Oxidation of MnO Atomic Layer Deposition Films. *Journal of the Electrochemical Society*, **2015**, 162, A2753-A2761	3.9	33
365	Charge Storage in Cation Incorporated □MnO2. *Chemistry of Materials*, **2015**, 27, 1172-1180	9.6	93
364	Atomic layer etching of Al2O3 using sequential, self-limiting thermal reactions with Sn(acac)2 and hydrogen fluoride. *ACS Nano*, **2015**, 9, 2061-70	16.7	104
363	Utilization of Al2O3Atomic Layer Deposition for Li Ion Pathways in Solid State Li Batteries. *Journal of the Electrochemical Society*, **2015**, 162, A344-A349	3.9	25
362	Waterless TiO2 atomic layer deposition using titanium tetrachloride and titanium tetraisopropoxide. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2014**, 32, 01A114	2.9	9
361	Amorphous vanadium oxide coating on graphene by atomic layer deposition for stable high energy lithium ion anodes. *Chemical Communications*, **2014**, 50, 10703-6	5.8	52

360	Ultra-thin 3D nano-devices from atomic layer deposition on polyimide. *Advanced Materials*, **2014**, 26, 3962-7	24	17
359	Growth and properties of hafnicone and HfO(2)/hafnicone nanolaminate and alloy films using molecular layer deposition techniques. *ACS Applied Materials & Interfaces*, **2014**, 6, 16880-7	9.5	35
358	Synthesis of ZnO quantum dot/graphene nanocomposites by atomic layer deposition with high lithium storage capacity. *Journal of Materials Chemistry A*, **2014**, 2, 7319-7326	13	109
357	Growth of Zircone on Nanoporous Alumina Using Molecular Layer Deposition. *Jom*, **2014**, 66, 649-653	2.1	7
356	Atomic Layer Deposition of Platinum Nanoparticles on Titanium Oxide and Tungsten Oxide Using Platinum(II) Hexafluoroacetylacetonate and Formalin as the Reactants. *Journal of Physical Chemistry C*, **2014**, 118, 8960-8970	3.8	27
355	Porous Fe2O3 nanorods anchored on nitrogen-doped graphenes and ultrathin Al2O3 coating by atomic layer deposition for long-lived lithium ion battery anode. *Carbon*, **2014**, 76, 141-147	10.4	42
354	Hemispherical micro-resonators from atomic layer deposition. *Journal of Micromechanics and Microengineering*, **2014**, 24, 125028	2	12
353	Oxidation Kinetics of Calcium Films by Water Vapor and Their Effect on Water Vapor Transmission Rate Measurements. *Journal of Physical Chemistry C*, **2014**, 118, 29322-29332	3.8	7
352	In situ transmission electron microscopy probing of native oxide and artificial layers on silicon nanoparticles for lithium ion batteries. *ACS Nano*, **2014**, 8, 11816-23	16.7	90
351	Reversible high-capacity Si nanocomposite anodes for lithium-ion batteries enabled by molecular layer deposition. *Advanced Materials*, **2014**, 26, 1596-601	24	146
350	GaN nanowire coated with atomic layer deposition of tungsten: a probe for near-field scanning microwave microscopy. *Nanotechnology*, **2014**, 25, 415502	3.4	4
349	Unexpected high power performance of atomic layer deposition coated Li[Ni1/3Mn1/3Co1/3]O2 cathodes. *Journal of Power Sources*, **2014**, 254, 190-197	8.9	66
348	Atomic layer deposition □Al2O3 diffusion barriers to eliminate the memory effect in beta-gamma radioxenon detectors. *Journal of Radioanalytical and Nuclear Chemistry*, **2013**, 296, 541-549	1.5	7
347	Molecular layer deposition on carbon nanotubes. *ACS Nano*, **2013**, 7, 7812-23	16.7	25
346	Metal-insulator-metal diodes: role of the insulator layer on the rectification performance. *Advanced Materials*, **2013**, 25, 1301-8	24	47
345	Ultralow thermal conductivity of atomic/molecular layer-deposited hybrid organic-inorganic zincone thin films. *Nano Letters*, **2013**, 13, 5594-9	11.5	82
344	H2O vapor transmission rate through polyethylene naphthalate polymer using the electrical Ca test. *Journal of Physical Chemistry A*, **2013**, 117, 12026-34	2.8	19
343	Pseudocapacitance of Amorphous TiO2 Thin Films Anchored to Graphene and Carbon Nanotubes Using Atomic Layer Deposition. *Journal of Physical Chemistry C*, **2013**, 117, 22497-22508	3.8	95

342	ZnO quantum dots-graphene composite for efficient ultraviolet sensing. *Materials Letters*, **2013**, 112, 165-168	3.3	15
341	Molecular Layer Deposition of Zircone and ZrO2/Zircone Alloy Films: Growth and Properties. *Chemical Vapor Deposition*, **2013**, 19, 204-212		52
340	History of atomic layer deposition and its relationship with the American Vacuum Society. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2013**, 31, 050818	2.9	73
339	Alucone interlayers to minimize stress caused by thermal expansion mismatch between Al□□films and Teflon substrates. *ACS Applied Materials & Interfaces*, **2013**, 5, 1165-73	9.5	42
338	Pyrolysis of Titanicone Molecular Layer Deposition Films as Precursors for Conducting TiO2/Carbon Composite Films. *Journal of Physical Chemistry C*, **2013**, 117, 17442-17450	3.8	42
337	Growth and Properties of Hybrid Organic-Inorganic Metalcone Films Using Molecular Layer Deposition Techniques. *Advanced Functional Materials*, **2013**, 23, 532-546	15.6	109
336	Unexpected Improved Performance of ALD Coated LiCoO2/Graphite Li-Ion Batteries. *Advanced Energy Materials*, **2013**, 3, 213-219	21.8	174
335	(Invited) In Situ Characterization of Plasma-Assisted Pt ALD on W ALD Adhesion Layers with Spectroscopic Ellipsometry. *ECS Transactions*, **2013**, 58, 19-26	1	4
334	Capillary evaporation on micromembrane-enhanced microchannel wicks with atomic layer deposited silica. *Applied Physics Letters*, **2013**, 103, 151602	3.4	34
333	Hybrid organic-inorganic films fabricated using atomic and molecular layer deposition **2013**,		1
332	Evaluating Al2O3 gas diffusion barriers grown directly on Ca films using atomic layer deposition techniques. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2013**, 31, 01A122	2.9	28
331	Ion-Exchangeable Functional Binders and Separator for High Temperature Performance of Li1.1Mn1.86Mg0.04O4Spinel Electrodes in Lithium Ion Batteries. *Journal of the Electrochemical Society*, **2013**, 160, A2234-A2243	3.9	20
330	Atomic layer deposition of amorphous TiO2 on graphene as an anode for Li-ion batteries. *Nanotechnology*, **2013**, 24, 424002	3.4	74
329	Ultrathin oxide films by atomic layer deposition on graphene. *Nano Letters*, **2012**, 12, 3706-10	11.5	66
328	Nanoscale Interface Modification of LiCoO2by Al2O3Atomic Layer Deposition for Solid-State Li Batteries. *Journal of the Electrochemical Society*, **2012**, 159, A1120-A1124	3.9	140
327	Atomic Layer Deposition of TiO2on Graphene for Supercapacitors. *Journal of the Electrochemical Society*, **2012**, 159, A364-A369	3.9	167
326	Molecular Layer Deposition of Titanicone Films using TiCl4 and Ethylene Glycol or Glycerol: Growth and Properties. *Chemistry of Materials*, **2012**, 24, 2854-2863	9.6	89
325	Three-dimensional Ni/TiO2 nanowire network for high areal capacity lithium ion microbattery applications. *Nano Letters*, **2012**, 12, 655-60	11.5	212

324	Alucone Alloys with Tunable Properties Using Alucone Molecular Layer Deposition and Al2O3 Atomic Layer Deposition. *Journal of Physical Chemistry C*, **2012**, 116, 3250-3257	3.8	100
323	MOSFETs Made From GaN Nanowires With Fully Conformal Cylindrical Gates. *IEEE Nanotechnology Magazine*, **2012**, 11, 479-482	2.6	27
322	Spatial atomic layer deposition: A route towards further industrialization of atomic layer deposition. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2012**, 30, 010802	2.9	248
321	Highly Conductive and Transparent Hybrid Organic□horganic Zincone Thin Films Using Atomic and Molecular Layer Deposition. *Journal of Physical Chemistry C*, **2012**, 116, 24784-24791	3.8	69
320	Molecular Layer Deposition of Hybrid Organic□horganic Films **2012**, 83-107		6
319	Improved Functionality of Lithium-Ion Batteries Enabled by Atomic Layer Deposition on the Porous Microstructure of Polymer Separators and Coating Electrodes. *Advanced Energy Materials*, **2012**, 2, 1022-1027	21.8	182
318	Evaluating operating conditions for continuous atmospheric atomic layer deposition using a multiple slit gas source head. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2012**, 30, 01A136	2.9	21
317	Critical tensile strain and water vapor transmission rate for nanolaminate films grown using Al2O3 atomic layer deposition and alucone molecular layer deposition. *Applied Physics Letters*, **2012**, 101, 234103	3.4	38
316	Growth of continuous and ultrathin platinum films on tungsten adhesion layers using atomic layer deposition techniques. *Applied Physics Letters*, **2012**, 101, 111601	3.4	41
315	Al2O3 and TiO2 atomic layer deposition on copper for water corrosion resistance. *ACS Applied Materials & Interfaces*, **2011**, 3, 4593-601	9.5	207
314	Molecular layer deposition of aluminum alkoxide polymer films using trimethylaluminum and glycidol. *Langmuir*, **2011**, 27, 15155-64	4	39
313	Using atomic layer deposition to hinder solvent decomposition in lithium ion batteries: first-principles modeling and experimental studies. *Journal of the American Chemical Society*, **2011**, 133, 14741-54	16.4	152
312	Ultrathin coatings on nano-LiCoO2 for Li-ion vehicular applications. *Nano Letters*, **2011**, 11, 414-8	11.5	322
311	Critical tensile and compressive strains for cracking of Al2O3 films grown by atomic layer deposition. *Journal of Applied Physics*, **2011**, 109, 084305	2.5	146
310	In-situ inspection of cracking in atomic-layer-deposited barrier films on surface and in buried structures. *Thin Solid Films*, **2011**, 520, 251-257	2.2	20
309	Electrochemical effects of ALD surface modification on combustion synthesized LiNi1/3Mn1/3Co1/3O2 as a layered-cathode material. *Journal of Power Sources*, **2011**, 196, 3317-3324	8.9	178
308	Analysis of high-Q, gallium nitride nanowire resonators in response to deposited thin films. *Sensors and Actuators A: Physical*, **2011**, 165, 59-65	3.9	10
307	Fe3O4 Nanoparticles Confined in Mesocellular Carbon Foam for High Performance Anode Materials for Lithium-Ion Batteries. *Advanced Functional Materials*, **2011**, 21, 2430-2438	15.6	370

306	Molybdenum Atomic Layer Deposition Using MoF6 and Si2H6 as the Reactants. *Chemistry of Materials*, **2011**, 23, 1668-1678	9.6	37
305	ALD tungsten NEMS switches and tunneling devices. *Sensors and Actuators A: Physical*, **2011**, 166, 269-276	3.9	22
304	Atomic layer deposition enabled interconnect technology for vertical nanowire arrays. *Sensors and Actuators A: Physical*, **2011**, 165, 107-114	3.9	4
303	Investigation of the defect density in ultra-thin Al2O3 films grown using atomic layer deposition. *Surface and Coatings Technology*, **2011**, 205, 3334-3339	4.4	38
302	Using a slit doser to probe gas dynamics during Al2O3 atomic layer deposition and to fabricate laterally graded Al2O3 layers. *Thin Solid Films*, **2011**, 519, 3612-3618	2.2	2
301	HWCVD MoO3 nanoparticles and a-Si for next generation Li-ion anodes. *Thin Solid Films*, **2011**, 519, 4495-4497	2.2	21
300	Surface poisoning in the nucleation and growth of palladium atomic layer deposition with Pd(hfac)2 and formalin. *Thin Solid Films*, **2011**, 519, 5339-5347	2.2	46
299	Metalcones: hybrid organic-inorganic films fabricated using atomic and molecular layer deposition techniques. *Journal of Nanoscience and Nanotechnology*, **2011**, 11, 7948-55	1.3	61
298	Nucleation and growth of Pt atomic layer deposition on Al2O3 substrates using (methylcyclopentadienyl)-trimethyl platinum and O2 plasma. *Journal of Applied Physics*, **2011**, 109, 084333	2.5	87
297	Effects of Atomic Layer Deposition of Al2O3 on the Li[Li0.20Mn0.54Ni0.13Co0.13]O2 Cathode for Lithium-Ion Batteries. *Journal of the Electrochemical Society*, **2011**, 158, A1298	3.9	108
296	Progress and future directions for atomic layer deposition and ALD-based chemistry. *MRS Bulletin*, **2011**, 36, 865-871	3.2	145
295	Metalcone and Metalcone/Metal Oxide Alloys Grown Using Atomic and Molecular Layer Deposition. *ECS Transactions*, **2011**, 41, 131-138	1	20
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